

Diamond-Based Photon BPMs for Fast Electron-Beam Diagnostics in Synchrotron Radiation Sources

M. Antonelli, G. Cautero, D. Giuressi, S. Lizzit, R. H. Menk

A. De Sio, E. Pace

M. Di Fraia

(Elettra-Sincrotrone Trieste S.C.p.A., Trieste, Italy)

(Università degli Studi di Firenze, Firenze, Italy)

(Università degli Studi di Trieste, Trieste, Italy)

MOTIVATION

Electron-beam monitoring and stabilization are primary concerns in modern Synchrotron Radiation facilities, typically equipped with a **Fast Orbit FeedBack** (FOFB) based on the **electron Beam-Position Monitors** (eBPMs). Nevertheless, the photon beam exhibits **residual position and intensity fluctuations**.

These phenomena can be detected by fast **photon Beam Position Monitors** (pBPMs). The information provided by these detectors is **useful** for the **electron-beam diagnostics** and it can be integrated into the FOFB.

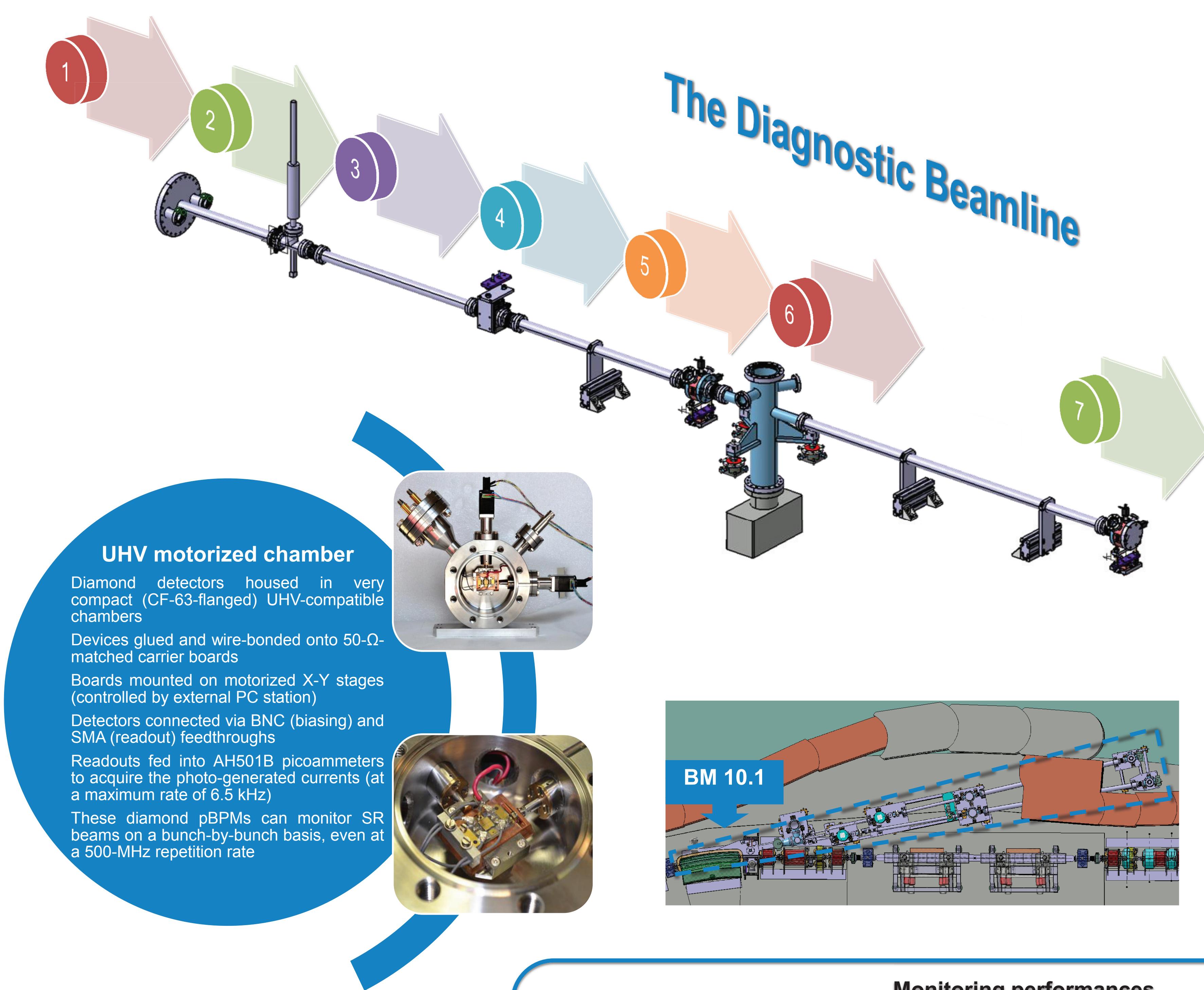
Amongst the available technologies for pBPMs, **single-crystal CVD diamond** is one of the most suitable materials thanks to its **outstanding physical properties** (high radiation hardness, semitransparency to X-rays, low thermal noise, high electron and hole mobility).

SOLUTION

A **diagnostic beamline** has been built at the exit of one of Elettra's bending magnets, with the aim of providing Elettra's future **FOFB** with **additional information** coming from state-of-the-art diamond pBPMs.

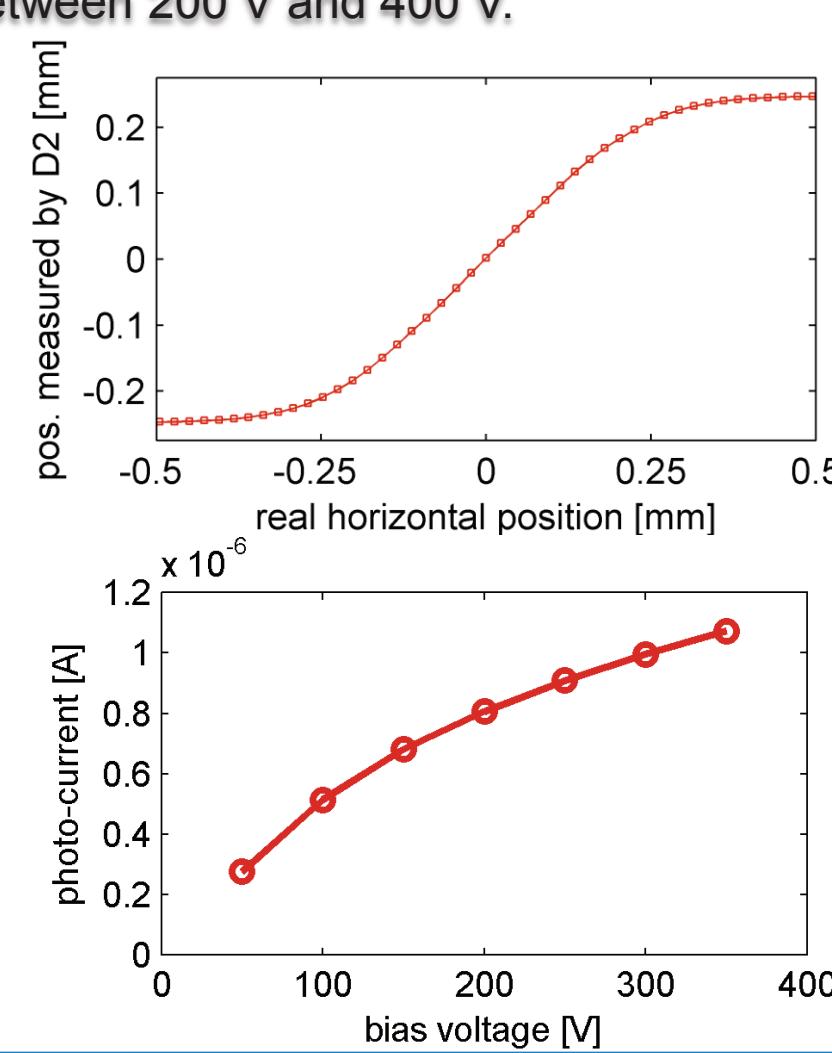
This line has been accommodated inside the shielding wall of the storage ring, between lines 10.1L and 10.1R, by exploiting the **central dead-end outlet** at the bending-magnet front end 10.1 in order to continuously **monitor the photon beam** without interfering with normal beamline operations.

This beamline features a 2-mm-thick water-cooled Al window, a remotely controlled shutter, a motorized slit system, an upstream pBPM (D1) and a downstream pBPM (D2). Outside the shielding wall, a **PC-based control system** allows acquiring and processing pBPM data. It also controls motors and biasing modules.

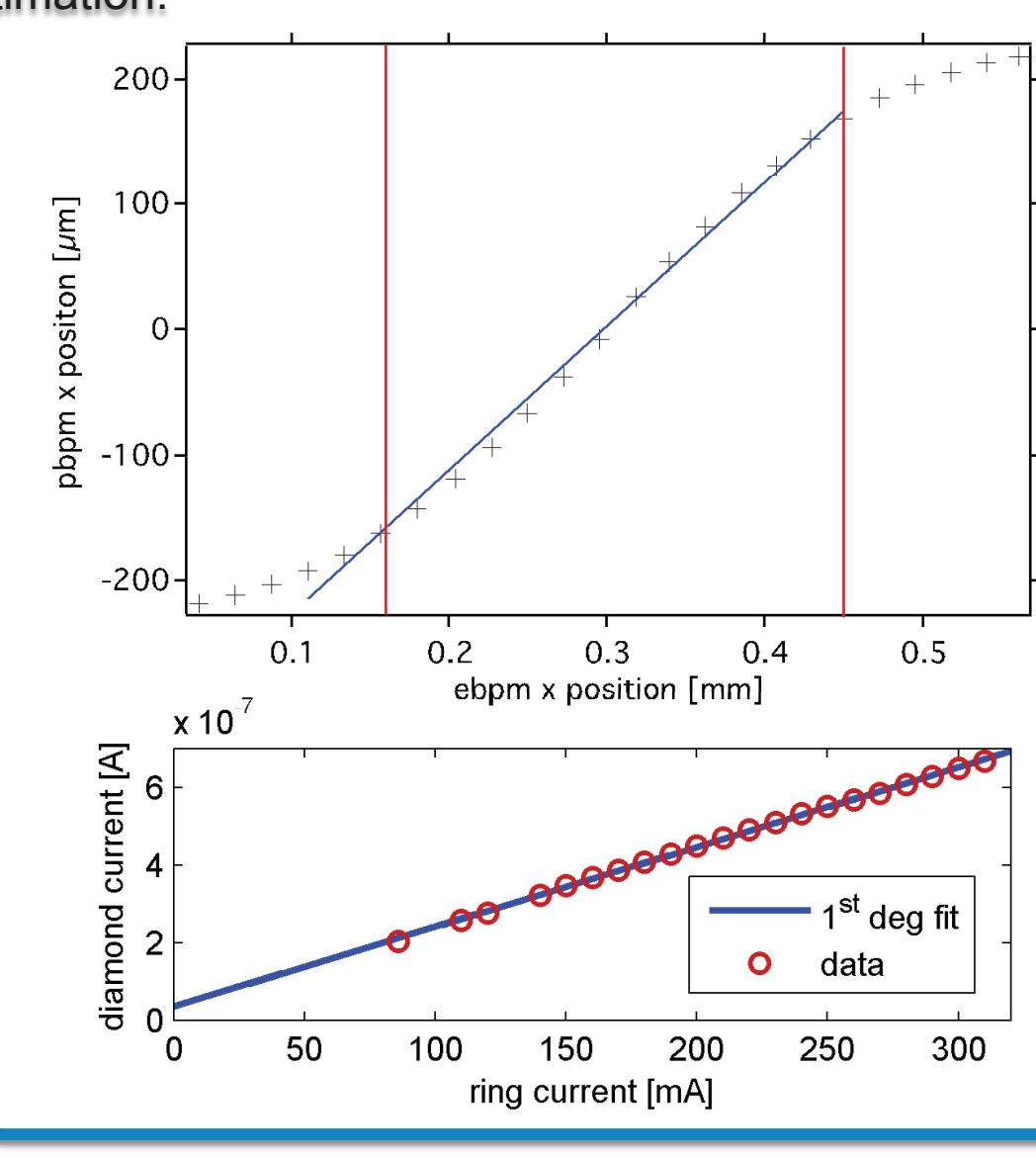


Monitoring performances

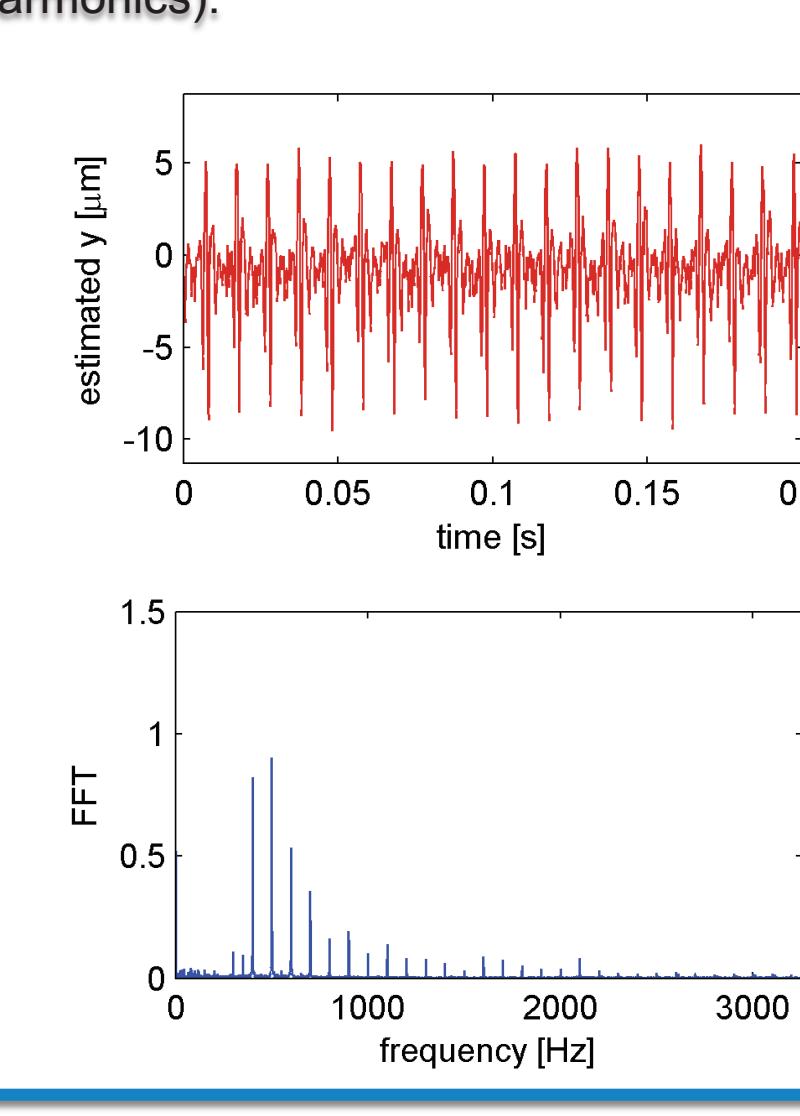
Preliminary pBPMs characterization
D2 moved w.r.t. the stationary photon beam by using the stepper motors of its UHV chamber. 124-nm precision in position estimation at a sampling rate of 10 Hz.
If projected to 10-kHz operations it gives a 3.9-μm precision. However, the deviation in this results is dominated by systematic errors (stepping precision, slow beam fluctuations). Saturation-curve measurements show a good operation range between 200 V and 400 V.



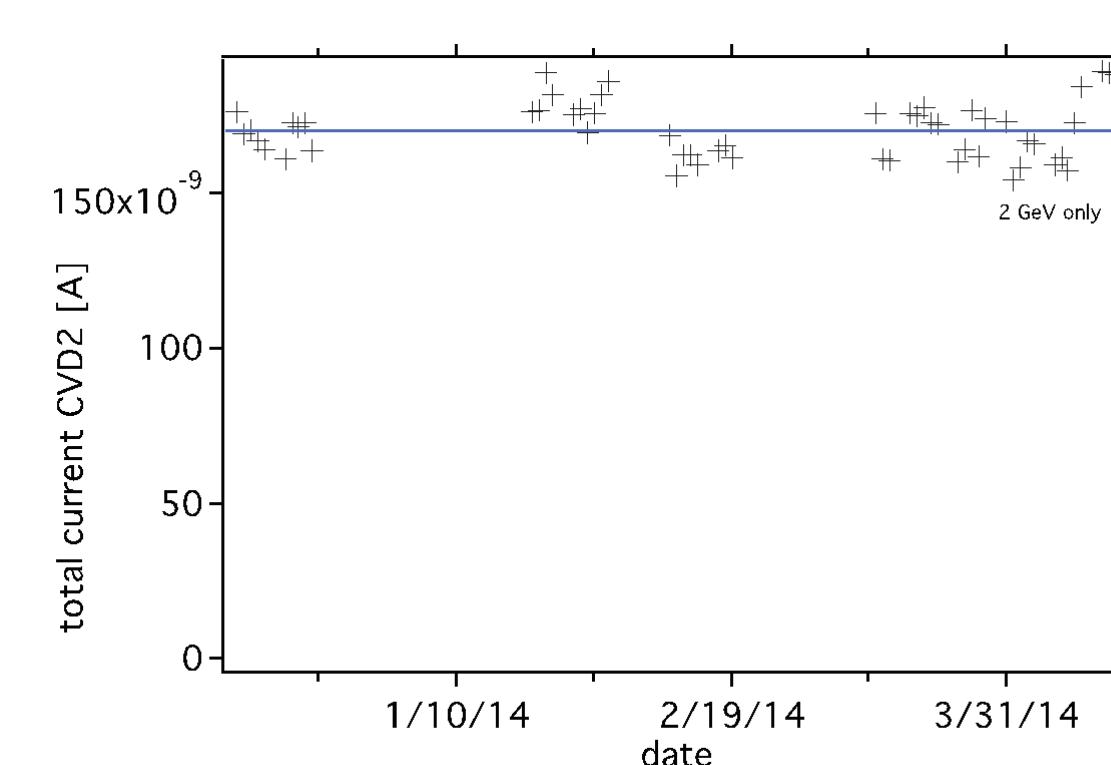
Deliberate electron-beam motion and current ramping
Comparison between pBPM and eBPM estimated positions. Linear range of about 400 μm.
Quasi-periodic deviation from linear trend (imputable to the optics-simulation algorithm used by the machine control system). Current-monitoring deviation within 1% w.r.t. eBPM estimation.



Fast monitoring
Stationary centred beam monitored in normal operations at a 6.5-kHz acquisition rate.
Stochastic uncertainty of 500 nm, considered as resolution limit for the system in these conditions.
Periodic fluctuation of 2 μm RMS.
A number of systematic components contributing to such fluctuations revealed by FFT (17 Hz and 23.5 Hz, 100 Hz and harmonics).



Long-term stability
20 nA and 0.19 μA read from D1 and D2, respectively (for a 300-mA machine current).
Precision in intensity monitoring better than 1%.
Sparse data available on radiation damage of this kind of CVDs caused by long-term exposure with x-rays.
Demonstrator operated continuously over a period of 9 months.
Total intensity measured by D2 reasonably constant over the span of time.



REFERENCES

- M. Antonelli et al., Proceedings of SPIE 8504, San Diego, USA, 85040D, 2012.
M. Antonelli et al., Nuclear Instruments and Methods A 730, 164 (2013).
A. De Sio et al., Diamond and Related Materials 34, 36 (2013).

FUTURE WORK

- Upgrade of the readout electronics to acquire at 10 kHz (to integrate pBPM information into the FOFB)
Increase of the vertical aperture of the slits (to allow more photons in and exploit D1 in vertical monitoring)
In-house device fabrication (i.e. metallization process and wire bonding)